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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/712,333	11/13/2003	Kaoru Koike	09792909-5759	1181
26263	7590	02/23/2005	EXAMINER	
SONNENSCHEIN NATH & ROSENTHAL LLP			COLEMAN, WILLIAM D	
P.O. BOX 061080			ART UNIT	PAPER NUMBER
WACKER DRIVE STATION, SEARS TOWER				
CHICAGO, IL 60606-1080			2823	

DATE MAILED: 02/23/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/712,333	KOIKE ET AL.	
	Examiner	Art Unit	
	W. David Coleman	2823	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 03 November 2003.
 2a) This action is FINAL. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 1-11 is/are pending in the application.
 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) 1-11 is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on 03 November 2003 is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. 10/080,104.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) Notice of References Cited (PTO-892)
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
 Paper No(s)/Mail Date _____

4) Interview Summary (PTO-413)
 Paper No(s)/Mail Date. _____
 5) Notice of Informal Patent Application (PTO-152)
 6) Other: _____

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

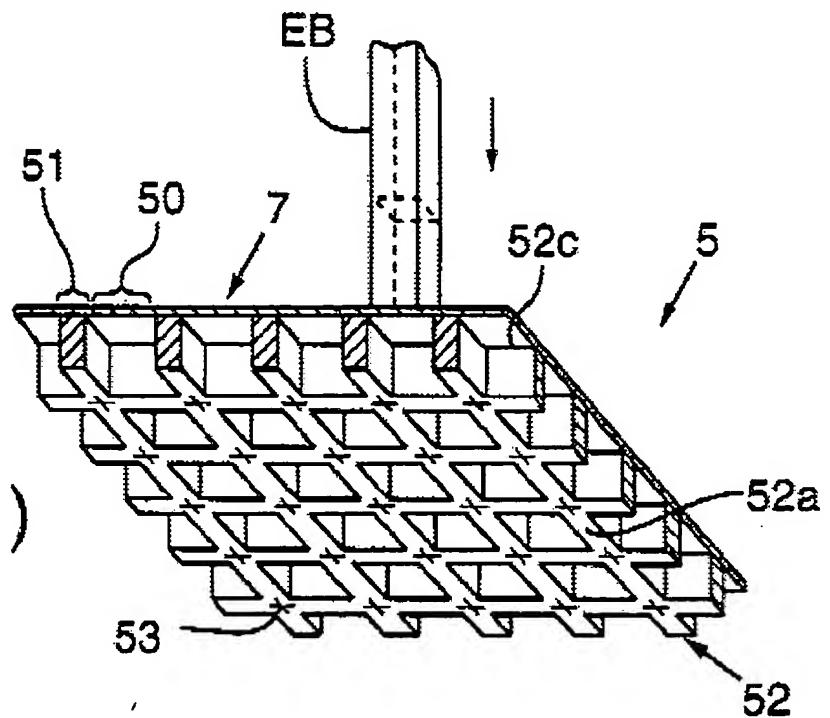
2. The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

3. Claims 1-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Yahiro et al., U.S. Patent 6,204,509 B1.

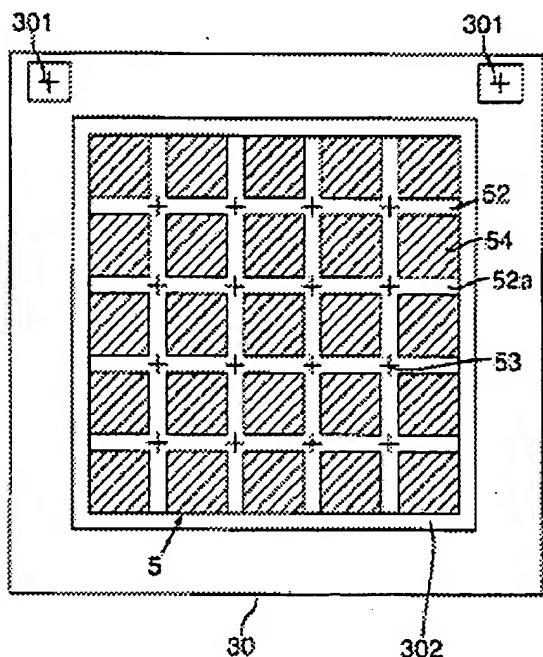
Yahiro discloses the invention as claimed. See FIGS. 1(a)-12, where Yahiro teaches the claimed limitations.

4. Pertaining to claim 1, Yahiro teaches a mask-making member comprising: a plurality of pattern formation regions **50** in which mask circuit patterns are to be formed; and a supporting region **51** in which any mask circuit pattern is not to be formed, said supporting region being provided for holding said plurality of pattern formation regions while separating said plurality of pattern formation regions from each other;

wherein said supporting region has first alignment marks 53 used at the time of exposure of a mask made from said mask-making member for forming said mask circuit patterns thereon, and second alignment marks 301 used at the time of exposure of a substrate to be exposed for forming circuit patterns thereon.



5. Pertaining to claim 2, Yahiro teaches a mask-making member according to claim 1, wherein said first alignment marks are formed in such a manner that one-or more of said first alignment marks 53 are located in a portion, around each of said plurality of pattern formation regions, of said supporting region, and said second alignment marks 301 are formed in such a manner as to be all located in a portion, outside an area formed by said plurality of said pattern formation regions, of said supporting region.



6. Pertaining to claim 3, Yahiro teaches a mask-making member according to claim 1, wherein shapes of said first alignment marks are different from those of said second alignment marks (please note that the Examiner takes the position that second alignment marks 301 have a rectangular shape around a cross-hair).
7. Pertaining to claim 4, Yahiro teaches a mask-making member according to claim 1, wherein said mask making member is a transmission mask-making member (well known when using a electron beam lithography technique).
8. Pertaining to claim 5, Yahiro teaches a mask-making member according to claim 1, wherein said mask making member is a stencil mask-making member (please note that the transfer of the image is a stencil type process).

9. Pertaining to claim 6, Yahiro teaches a mask-making member according to claim 4, wherein said first alignment marks and said second alignment marks are formed on an electron scatterer formed on a membrane.

10. Pertaining to claim 7, Yahiro teaches a mask-making member according to claim 4, wherein said first alignment marks and said second alignment marks are formed on an electron scatterer formed on a membrane by selectively removing said electron scatterer.

11. Pertaining to claim 8, Yahiro teaches a mask-making member according to claim 5, wherein said first alignment marks and said second alignment marks are formed on a mask board.

12. Pertaining to claim 9, Yahiro teaches a mask-making member according to claim 5, wherein said first alignment marks and said second alignment marks are formed on a mask board by selectively removing said mask board. (please note that the claims presented are product claims and not process claims and only patentable weight is given to the product).

13. Pertaining to claim 10, Yahiro teaches a mask-making member according to claim 5, wherein said first alignment marks and said second alignment marks are formed on a mask board by selectively removing said mask board to form holes or grooves in said mask board, and burying said holes or grooves in said mask board, and burying said holes or grooves with a metal

whose atoms have atomic weights heavier than those of atoms of said mask board (please see the reasoning to the rejection of claim 9 above).

14. Pertaining to claim 11, Yahiro teaches a mask-making member according to claim 10, wherein said metal is platinum, gold, silver, copper, tungsten, tantalum, or molybdenum (column 8, line 18).

Information Disclosure Statement

15. The listing of references in the specification is not a proper information disclosure statement. 37 CFR 1.98(b) requires a list of all patents, publications, or other information submitted for consideration by the Office, and MPEP § 609 A(1) states, "the list may not be incorporated into the specification but must be submitted in a separate paper." Therefore, unless the references have been cited by the examiner on form PTO-892, they have not been considered.

Drawings

16. Figure 1 should be designated by a legend such as --Prior Art-- because only that which is old is illustrated. See MPEP § 608.02(g). Corrected drawings in compliance with 37 CFR 1.121(d) are required in reply to the Office action to avoid abandonment of the application. The replacement sheet(s) should be labeled "Replacement Sheet" in the page header (as per 37 CFR 1.84(c)) so as not to obstruct any portion of the drawing figures. If the changes are not accepted by the examiner, the applicant will be notified and informed of any required corrective action in the next Office action. The objection to the drawings will not be held in abeyance.

Conclusion

17. Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. David Coleman whose telephone number is 571-272-1856.

The examiner can normally be reached on Monday-Friday 9:00 AM-5:30 PM.

18. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

19. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



W. David Coleman
Primary Examiner
Art Unit 2823

WDC